

WHAT IS CLAIMED IS:

1. A method of forming a patterned thin film,
wherein said thin film is not a monolayer, said process
5 comprising the step of:

depositing a thin film material on a surface of a
substrate having thereon a patterned underlayer of a
self-assembled monolayer.

10 2. The method of claim 1, wherein said substrate
is selected from the group consisting of: a metal, a
metal oxide, a semiconductor, a metal alloy, a
semiconductor alloy, a polymer, an organic solid, and a
combination thereof.

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3. The method of claim 2, wherein said substrate
is an irregularly shaped substrate.

4. The method of claim 2, wherein said substrate
20 is a solid substrate having a flexible, curved or
planar geometry.

5. The method of claim 1, wherein said self-
assembled monolayer has patterned and unpatterned
25 regions and is prepared by a process comprising the
steps of:

providing a stamp having a surface;

coating said surface of said stamp with an organic
molecular species to produce a coated surface, said
30 organic molecular species having a head functional
group capable of interacting with said surface of said

substrate, and a tail group for chemical differentiation of said patterned and unpatterned regions of said coated surface;

placing said coated surface in contact with said
5 substrate for a length of time sufficient to transfer said self-assembled monolayer of said organic molecular species from said stamp to said substrate; and
removing said stamp.

10 6. The method of claim 5, wherein said stamp is an elastomeric stamp.

7. The method of claim 5, wherein said stamp has at least one indented and at least one non-indented
15 surface.

8. The method of claim 7, wherein said transfer is in a pattern defined by the topography of said stamp.

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9. The method of claim 5, wherein said organic molecular species has a functional head group selected from the group consisting of: a phosphine, phosphonic acid, carboxylic acid, thiol, epoxide, amine, imine,
25 hydroxamic acid, phosphine oxide, phosphite, phosphate, phosphazine, azide, hydrazine, sulfonic acid, sulfide, disulfide, aldehyde, ketone, silane, germane, arsine, nitrile, isocyanide, isocyanate, thiocyanate, isothiocyanate, amide, alcohol (hydroxyl), selenol
30 (selenide), nitro, boronic acid, ether, thioether, carbamate, thiocarbamate, dithiocarbamate,

dithlocarboxylate, xanthate, thioxanthate, alkylthiophosphate, dialkyldithiophosphate, and a combination thereof.

5 10. The method of claim 5, wherein said organic molecular species has a functional tail group selected from the group consisting of: a hydrocarbon, partially halogenated hydrocarbon, fully halogenated hydrocarbon, phosphine, phosphonic acid, carboxylic acid, thiol,
10 epoxide, amine, imine, hydroxamic acid, phosphine oxide, phosphite, phosphate, phosphazine, azide, hydrazine, sulfonic acid, sulfide, disulfide, aldehyde, ketone, silane, germane, arsine, nitrile, isocyanide, isocyanate, thiocyanate, isothiocyanate, amide, alcohol
15 (hydroxyl), selenol (selenide), nitro, boronic acid, ether, thioether, carbamate, thiocarbamate, dithiocarbamate, dithlocarboxylate, xanthate, thioxanthate, alkylthiophosphate, dialkyldithiophosphate, and a combination thereof.

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 11. The method of claim 5, wherein said organic molecular species comprises one or more compounds selected from the group consisting of: a silane, a phosphonic acid, a carboxylic acid, a hydroxamic acid,
25 a thiol, an amine, a phosphine, a hydrocarbon, partially halogenated hydrocarbon and a fully halogenated hydrocarbon.

 12. The method of claim 5, wherein said organic
30 molecular species comprises (tridecafluoro-1,1,2,2-tetrahydrooctyl)trichlorosilane.

13. The method of claim 5, wherein said organic molecular species comprises octadecylphosphonic acid.

5 14. The method of claim 1, wherein said self-assembled monolayer has patterned and unpatterned regions and is prepared by a process comprising the steps of:

 contacting said substrate and a solution
10 comprising an organic molecular species having a head functional group capable of interacting with said surface of said substrate, and a tail group for chemical differentiation, said contacting being at a temperature and for a length of time sufficient to bind
15 said functional head groups to said surface of said substrate; and

 exposing said self-assembled molecular monolayer to radiation modulated spatially in intensity with a mask having one or more regions transparent to
20 radiation to chemically modify said self-assembled molecular monolayer in a chemically distinct pattern defined by said transparent regions of said mask.

 15. The method of claim 14, wherein said
25 radiation is light.

 16. The method of claim 14, wherein said mask is a photomask.

30 17. The method of claim 14, wherein said contacting is carried out by immersing said substrate

in said solution comprising said organic molecular species.

18. The method of claim 14, wherein said organic
5 molecular species has a functional head group selected
from the group consisting of: a phosphine, phosphonic
acid, carboxylic acid, thiol, epoxide, amine, imine,
hydroxamic acid, phosphine oxide, phosphite, phosphate,
phosphazine, azide, hydrazine, sulfonic acid, sulfide,
10 disulfide, aldehyde, ketone, silane, germane, arsine,
nitrile, isocyanide, isocyanate, thiocyanate,
isothiocyanate, amide, alcohol (hydroxyl), selenol
(selenide), nitro, boronic acid, ether, thioether,
carbamate, thiocarbamate, dithiocarbamate,
15 dithlocarboxylate, xanthate, thioxanthate,
alkylthiophosphate, dialkyldithiophosphate, and a
combination thereof.

19. The method of claim 14, wherein said organic
20 molecular species has a functional tail group selected
from the group consisting of: a hydrocarbon, partially
halogenated hydrocarbon, fully halogenated hydrocarbon,
phosphine, phosphonic acid, carboxylic acid, thiol,
epoxide, amine, imine, hydroxamic acid, phosphine
25 oxide, phosphite, phosphate, phosphazine, azide,
hydrazine, sulfonic acid, sulfide, disulfide, aldehyde,
ketone, silane, germane, arsine, nitrile, isocyanide,
isocyanate, thiocyanate, isothiocyanate, amide, alcohol
(hydroxyl), selenol (selenide), nitro, boronic acid,
30 ether, thioether, carbamate, thiocarbamate,
dithiocarbamate, dithlocarboxylate, xanthate,

thioxanthate, alkylthiophosphate,
dialkyldithiophosphate, and a combination thereof.

20. The method of claim 14, wherein said self-
5 assembled molecular monolayer comprises (tridecafluoro-
1,1,2,2-tetrahydrooctyl)trichlorosilane.

21. The method of claim 14, wherein said self-
assembled molecular monolayer comprises
10 octadecylphosphonic acid.

22. The method of claim 1, wherein said thin film
is deposited by a solution-based deposition process.

15 23. The method of claim 22, wherein said thin
film material is selected from the group consisting of:
an organic molecule, a short-chain organic oligomer, a
long-chain organic polymer, a photoresist, an organic-
inorganic hybrid material, a metallo-organic complex, a
20 nanoparticle of metal, a nanoparticle of metal oxide, a
nanoparticle of semiconductor, a silica particle, an
inorganic salt, and a mixture thereof.

24. The method of claim 23, wherein said organic-
25 inorganic hybrid material is selected from the group
consisting of: $(C_6H_5C_2H_4NH_3)_2SnI_4$, $(C_4H_9NH_3)_2CH_3NH_3Sn_2I_7$,
 $(C_6H_5C_2H_4NH_3)_2CH_3NH_3Sn_2I_7$, $(H_3NC_4H_8NH_3)_2SnI_4$ and a mixture
thereof.

30 25. The method of claim 23, wherein said
photoresist is a positive working, deep UV photoresist.

26. The method of claim 23, wherein said long-chain organic polymer is polymethyl methacrylate/methyl methacrylate copolymer.

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27. The method of claim 23, wherein said metallo-organic complex is tin 2-ethylhexanoate.

28. The method of claim 22, wherein said
10 solution-based deposition process is a spin-coating process comprising the steps of:

flooding said substrate having thereon said
patterned self-assembled molecular monolayer with a
solution comprising a thin film material or a precursor
15 thereof; and

spinning to deposit said thin film material
thereby forming a patterned thin film on said
substrate.

20 29. The method of claim 22, wherein said solution-based deposition process is an immersion-coating process comprising the steps of:

immersing said substrate having thereon said
patterned self-assembled molecular monolayer into a
25 solution comprising said thin film material, or a precursor thereof; and

withdrawing said substrate from said solution,
thereby forming a patterned thin film on said
substrate.

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